Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	5772	((wet adj3 etch\$3) or (etch\$3 adj3 sloution) or (liquid adj3 etch\$3)) with metal\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 13:39
L2	1703	L1 and (metal near5 thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 13:44
L4	389	L2 and ((exceed\$3 or larger or smaller) with thickness\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 13:57
L6	105	L4 and (undercut\$1 or notch\$2 or groove\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 14:07
L8	210	L2 and (etch\$3 with (thin near3 metal))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 13:56
L9	72	L4 and L8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 13:57
L10	31	L6 and L9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 13:57
L13	41	L9 not L10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 14:27
L14	2	L13 and chelat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 14:31



Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L15	36	L2 and chelat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 15:06
L16	120	L1 and chelat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 15:08
L17	84	L16 not L15	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 15:09
L19	46	L17 and (angstroms or nanometer\$1 or "nm")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 15:54
L21	38	L17 not L19	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 15:54

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L22	897	(((wet adj3 etch\$3) or (etch\$3 adj3 sloution) or (liquid adj3 etch\$3)) same metal\$1) and ((high adj K) or (high adj dielectric))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 16:13
L23	23	L22 and chelat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 17:06
L24	11	L23 not L10 not L17	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 17:20
L25	11210	((wet adj3 etch\$3) or (etch\$3 adj3 sloution) or (liquid adj3 etch\$3)) same metal\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 16:44
L26	198	L25 and chelat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/25 16:27